INTERNATIONAL SEARCH REPORT

International Application No

_ i/US2004/041884 A. CLASSIFICATION OF SUBJECT MATTER IPC 7 GO1N21/956 GO1B11/24 H01L21/66 G03F7/20 G06T7/00 G01N23/22 According to International Patent Classification (IPC) or to both national classification and IPC B. FIELDS SEARCHED Minimum documentation searched (classification system followed by classification symbols) GOIN GOIB HOIL GO3F GO6T IPC 7 Documentation searched other than minimum documentation to the extent that such documents are included in the fields searched Electronic data base consulted during the international search (name of data base and, where practical, search terms used) EPO-Internal, INSPEC, COMPENDEX C. DOCUMENTS CONSIDERED TO BE RELEVANT Category 9 Citation of document, with indication, where appropriate, of the relevant passages Relevant to claim No. US 6 480 807 B1 (MIYANO YUMIKO) X 1-15, 12 November 2002 (2002-11-12) 17 - 31, 33-38 column 2, line 61 - column 3, line 3 column 3, lines 20-28 column 6, lines 7-23 column 8, lines 5-45 Further documents are listed in the continuation of box C. Patent family members are listed in annex. Special categories of cited documents: "T" later document published after the international filing date or priority date and not in conflict with the application but "A" document defining the general state of the art which is not cited to understand the principle or theory underlying the considered to be of particular relevance invention "E" earlier document but published on or after the international "X" document of particular relevance; the claimed invention filing date cannot be considered novel or cannot be considered to involve an inventive step when the document is taken alone "L" document which may throw doubts on priority claim(s) or which is cited to establish the publication date of another "Y" document of particular relevance; the claimed invention citation or other special reason (as specified) cannot be considered to involve an inventive step when the *O* document referring to an oral disclosure, use, exhibition or document is combined with one or more other such docuother means ments, such combination being obvious to a person skilled in the art. document published prior to the International filing date but "&" document member of the same patent family later than the priority date claimed Date of the actual completion of the international search Date of mailing of the international search report 27/04/2005 15 April 2005 Name and mailing address of the ISA Authorized officer

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